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Atty. Dkt. No. 039153-0310 (F0797)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Calvin T. Gabriel et al.
Title: PROCESS FOR IMPROVING THE
ETCH STABILITY OF ULTRA-
THIN PHOTORESIST
Appl. No.: 09/819,552
Filing Date: 03/28/2001
Examiner: Unknown
Art Unit: 2812

<p>CERTIFICATE OF MAILING I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below.</p> <p><u>Deborah A. Kacrowski</u> (Printed Name)</p> <p><u>Deborah A. Kacrowski</u> (Signature)</p> <p><u>June 22, 2001</u> (Date of Deposit)</p>
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TRANSMITTAL OF FORMAL DRAWINGS

Commissioner for Patents
Washington, D.C. 20231

ATTENTION: DRAWING REVIEW BRANCH

Sir:

Transmitted herewith are the formal drawings (3 sheets, Figures 1-5) for the above-identified application. The Official Draftsperson is respectfully requested to approve these drawings for entry into the application.

Respectfully submitted,

Date

6/22/2001

By

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